Attorney Docket: 081468-0275503 Client Reference: P-0166.010-US

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REPLY UNDER 37 C.F.R. §1.116 EXPEDITED PROCEDURE TECHNOLOGY CENTER ART UNIT 2882

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 4742

CASTENMILLER et al.

Application No.: 09/739,622

Group Art Unit: 2882

Filed: December 20, 2000

Examiner: Ho, Allen

Title: POSITION MEASURING SYSTEM FOR USE IN LITHOGRAPHIC APPARATUS

(As Amended)

AMENDMENT AFTER FINAL REJECTION UNDER 37 C.F.R. §1.1122

Amendment After Final
ioner for Patents
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ia, VA 22313-1450

response to the Office Action detail I Mail Stop Amendment After Final Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated January 30, 2004, please amend the aboveidentified application as follows:

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

- 1. (Currently amended) A lithographic projection apparatus comprising:
 - a projection beam illumination system which supplies a projection beam of radiation;
- a first object table for holding a protection beam patterning device which patterns the projection beam according to a desired pattern;
 - a second object table for holding a substrate; and
- a projection system which images the patterned beam onto a target portion of the substrate;

a reference frame; and

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